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(12) **United States Design Patent**
Jang et al.

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(54) **OUTER WALL OF REACTOR FOR SEMICONDUCTOR MANUFACTURING APPARATUS**

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(**) Term: **15 Years**

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(30) **Foreign Application Priority Data**

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(51) **LOC (10) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/182**

(58) **Field of Classification Search**
USPC D13/182; D15/144, 144.2; D23/259, D23/260, 261, 262, 263, 264, 265, 233, D23/209, 235
CPC .. H01J 37/32642; H01J 37/32; H01J 37/3244; H01J 37/32449; H01J 37/32623; H01J 37/32633; C30B 25/14; C30B 25/16; C30B 25/165; C23C 16/00; C23C 16/4412; C23C 16/455; C23C 16/45563; C23C 16/45574; C23C 16/4558; C23C 16/45565; C23C 16/44; C23C 16/4401; C23C 16/4402; C23C 16/4404; C23C 16/4408; C23C 16/45517; C23C 16/45519; C23C 16/45521; C23C 16/45559; C23C 16/45568; C23C 16/4557; C23C 16/45587; C23C 16/458; H01L 21/67; H01L 21/67011; H01L 21/67063; H01L 21/67069; H01L 21/6708; H01L 21/68098; H01L 21/67109; H01L 21/68714; F27B 15/00; F27B 15/006; F27B 15/10; F27D 5/0037; F27D 5/02; F27D 5/00; F27D 5/023
See application file for complete search history.

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(57) **CLAIM**

The ornamental design for an outer wall of a reactor for a semiconductor manufacturing apparatus, as shown and described.

DESCRIPTION

FIG. **1** is a perspective view of an outer wall of a reactor for a semiconductor manufacturing apparatus, showing our new design;
FIG. **2** is a front elevational view thereof;
FIG. **3** is a rear elevational view thereof;
FIG. **4** is a left side elevational view thereof;
FIG. **5** is a right side elevational view thereof;
FIG. **6** is a top plan view thereof;
FIG. **7** is a bottom plan view thereof;
FIG. **8** is a cross sectional view taken along line **8-8** of FIG. **6**; and,
FIG. **9** is a cross sectional view taken along line **9-9** of FIG. **6**.

The broken lines shown in the drawings represent portions of the outer wall of a reactor for a semiconductor manufacturing apparatus that form no part of the claimed design.

1 Claim, 6 Drawing Sheets

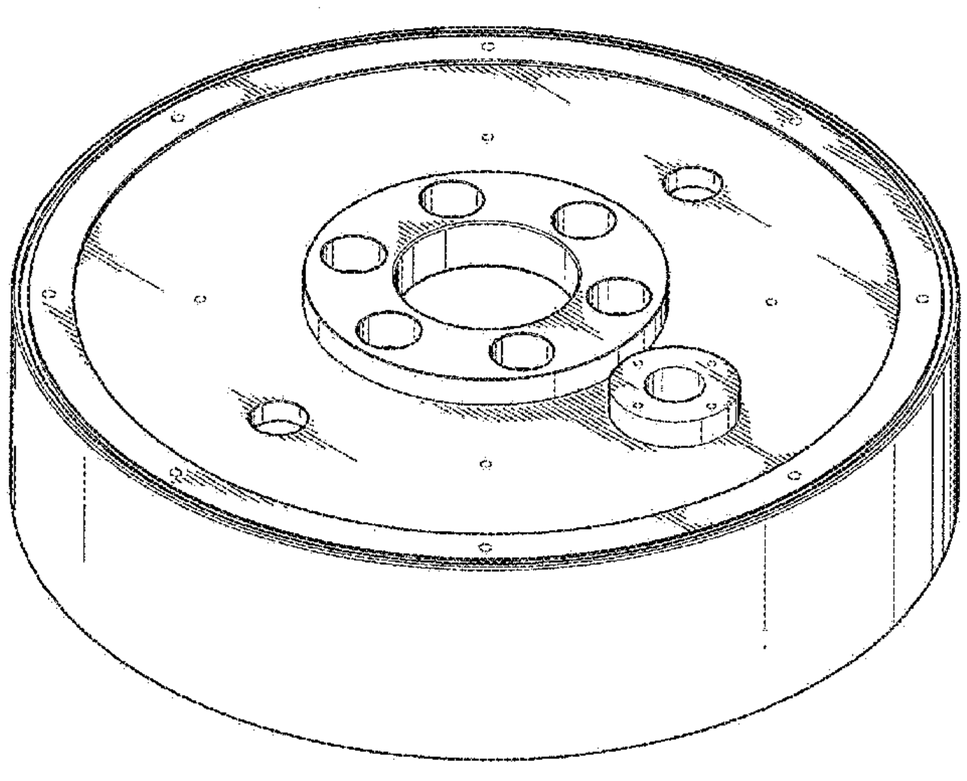

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FIG. 1

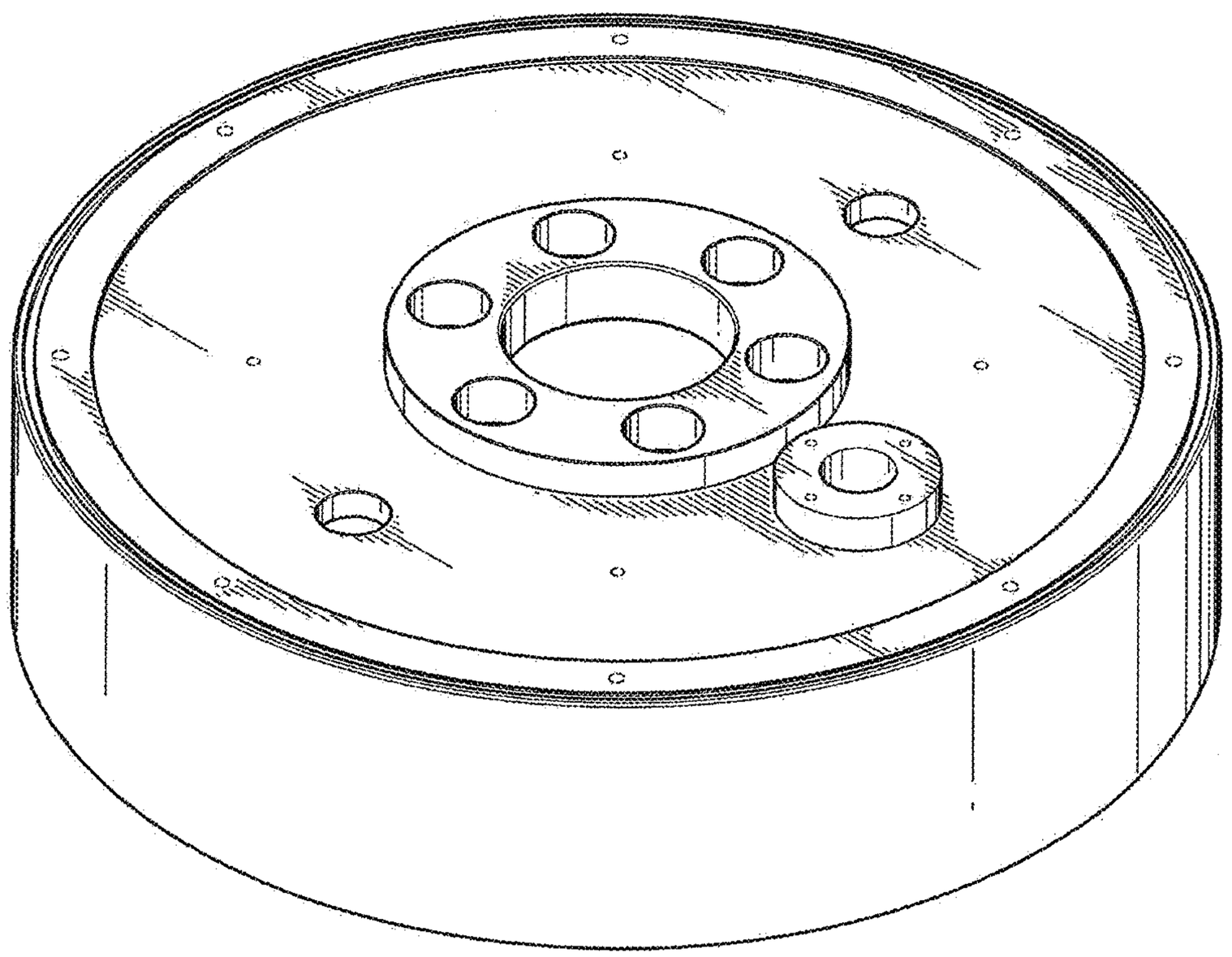

FIG. 2

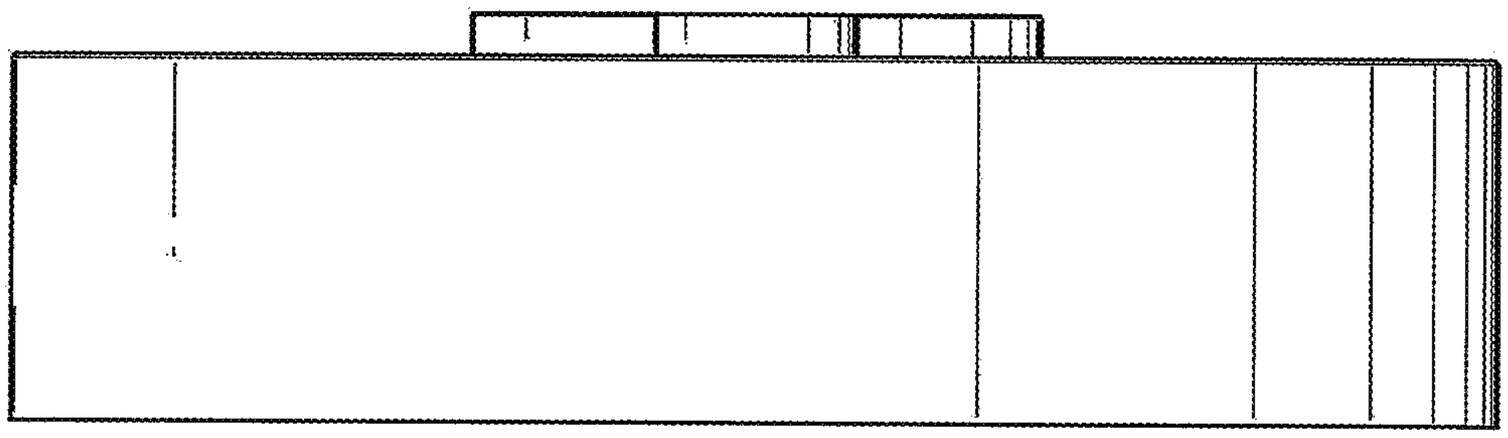

FIG. 3

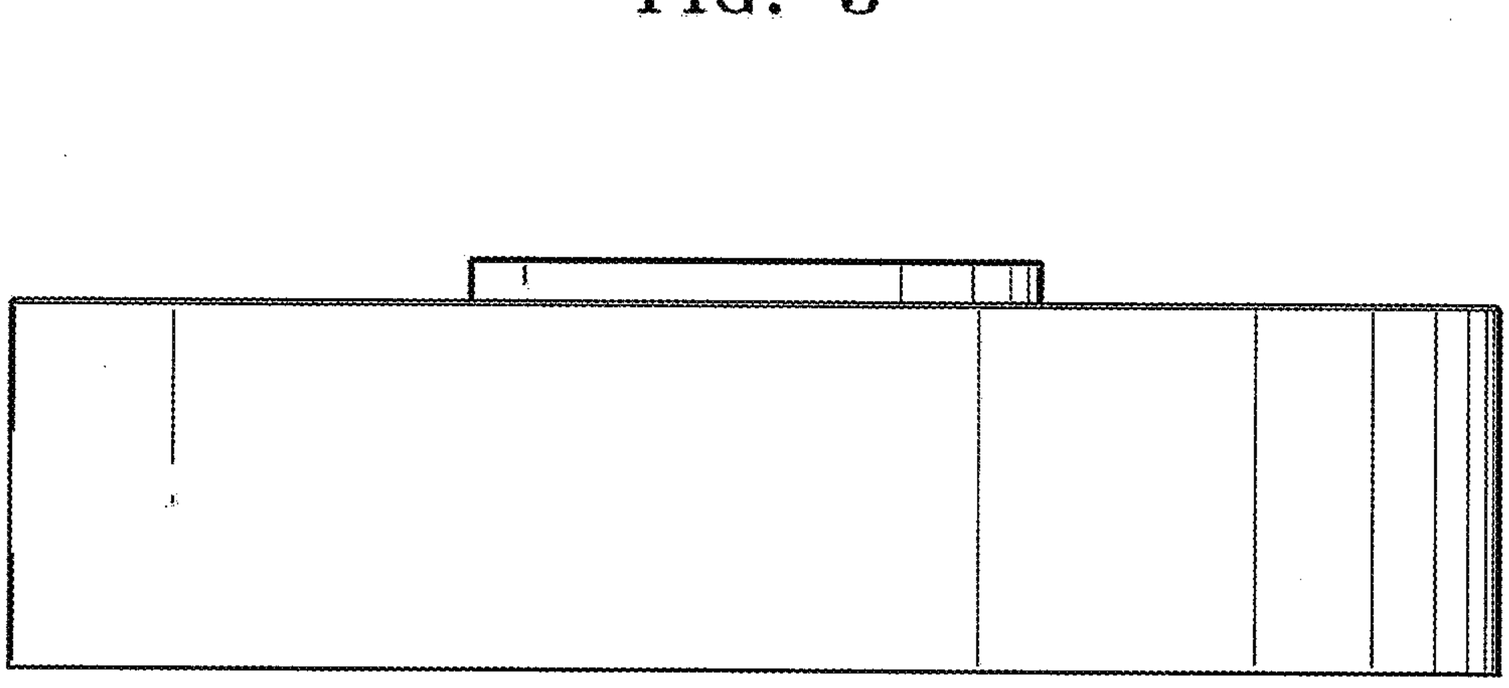

FIG. 4

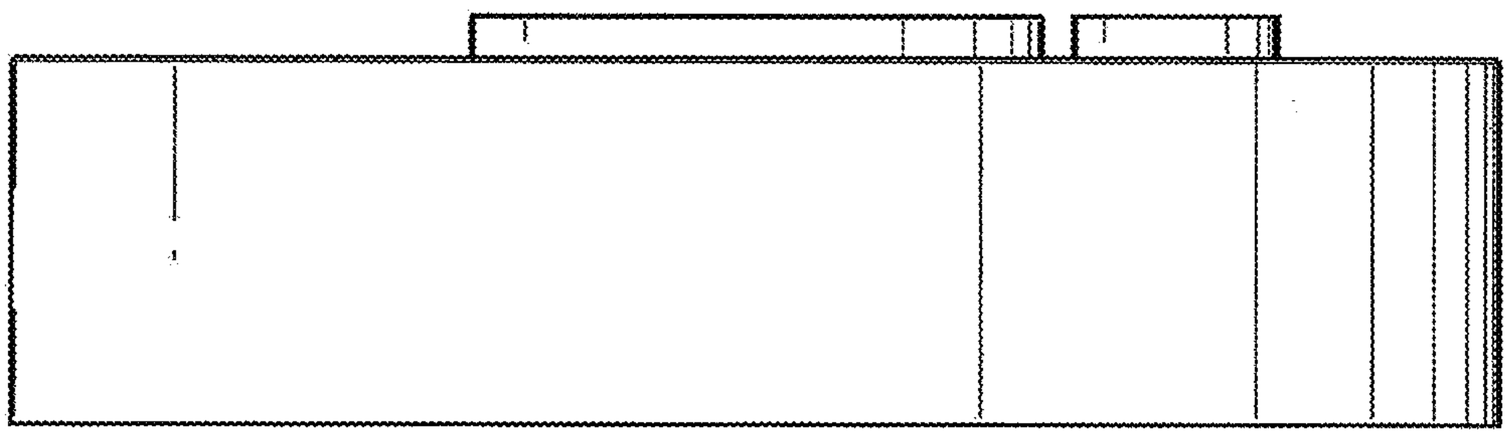

FIG. 5

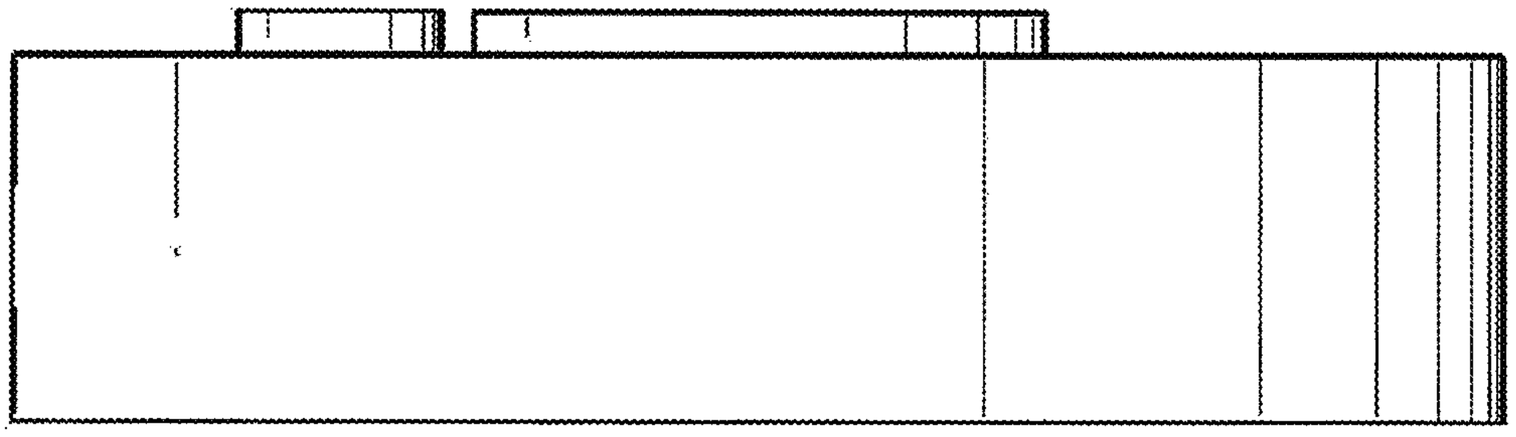

FIG. 6

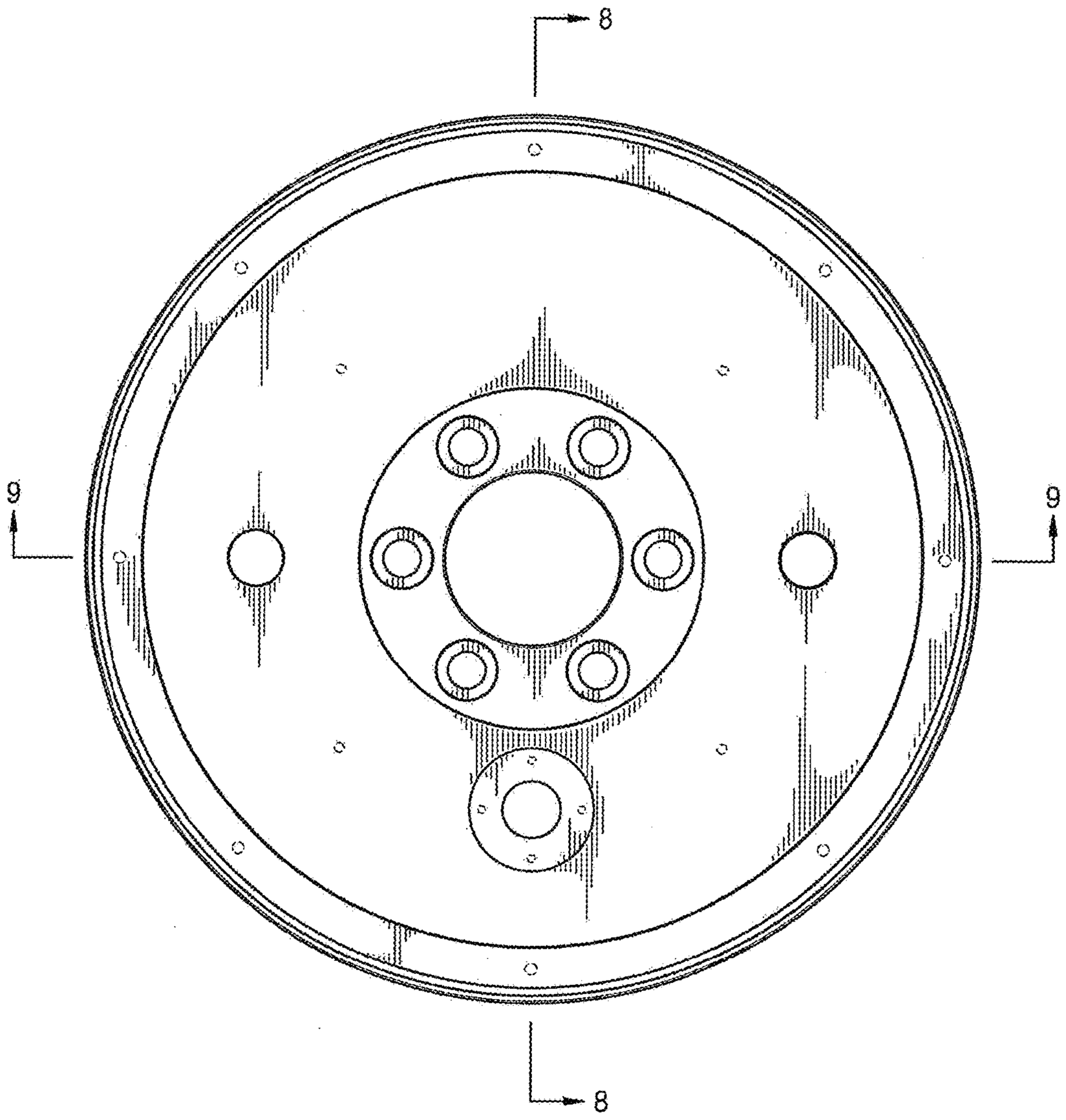

FIG. 7

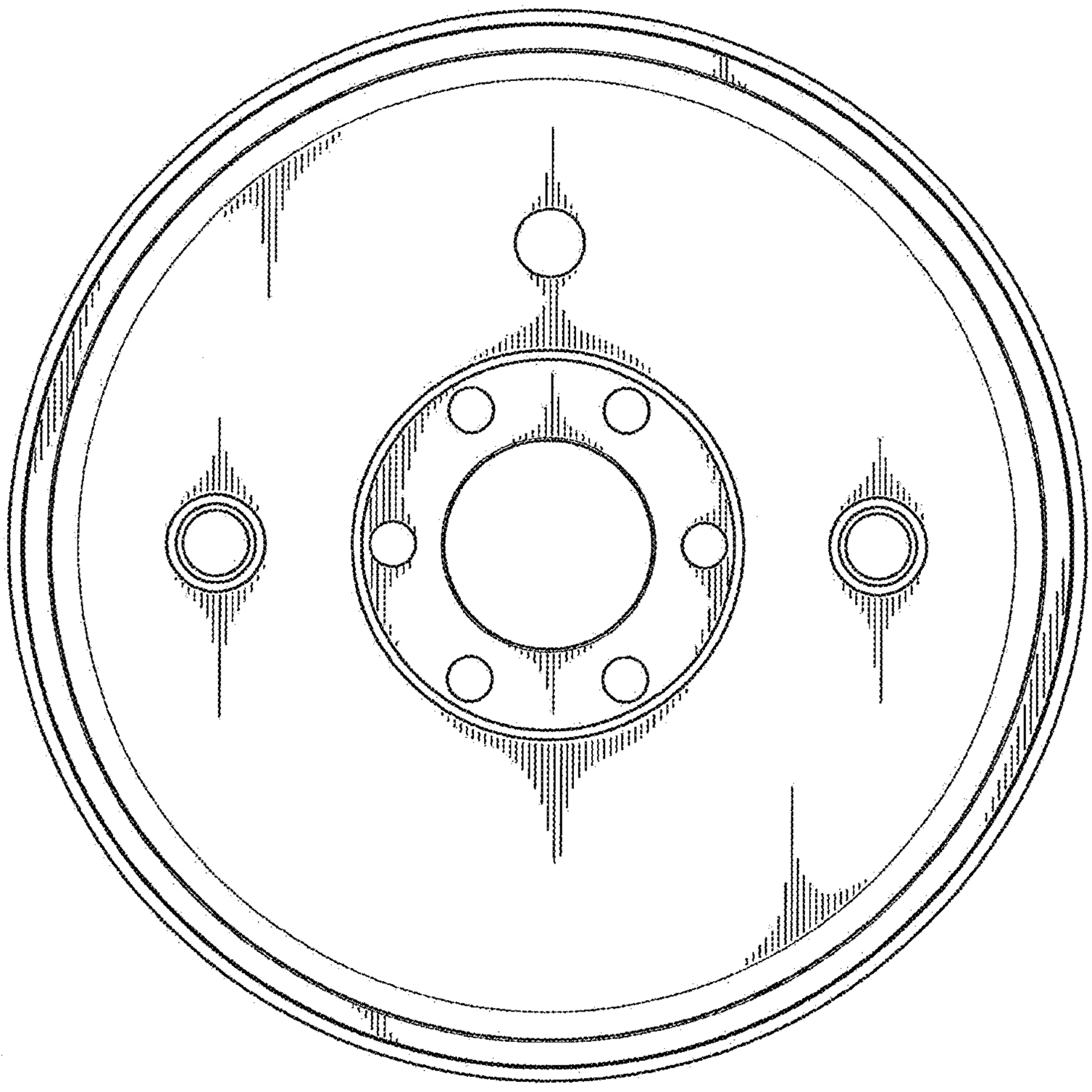

FIG. 8

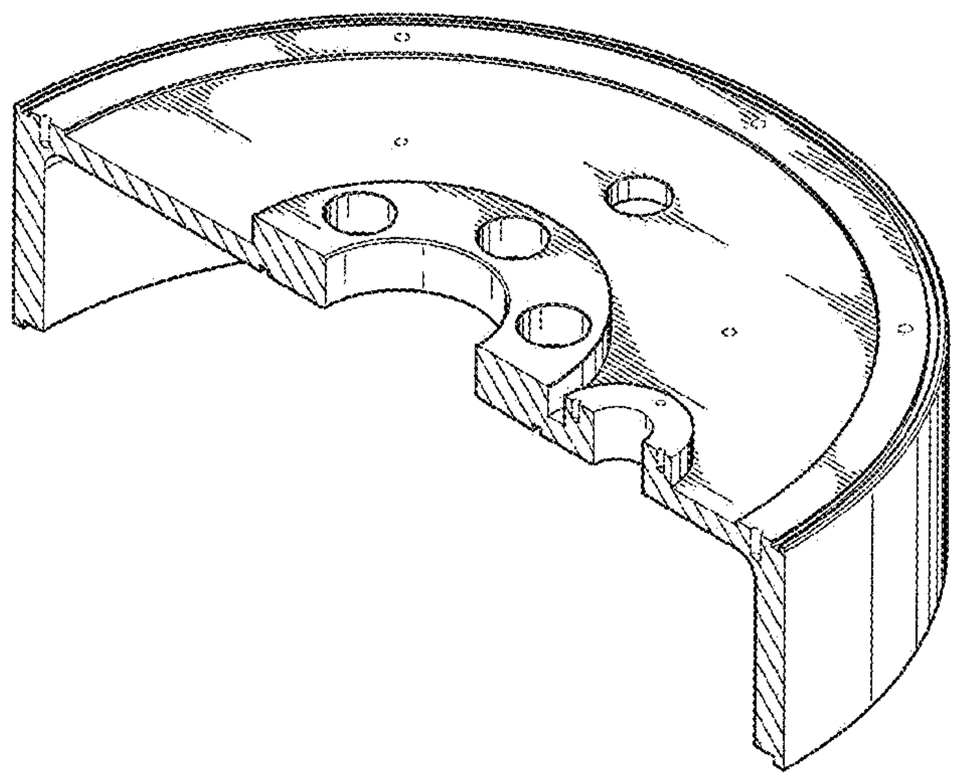

FIG. 9